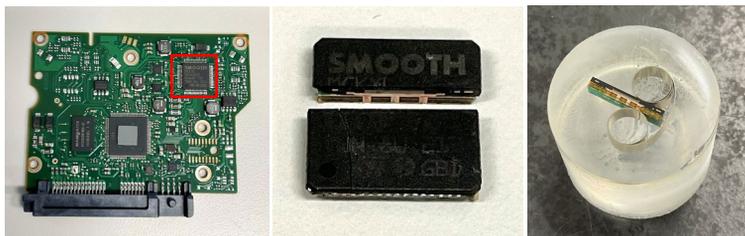


古いHDD基盤のICチップ断面 マッピング

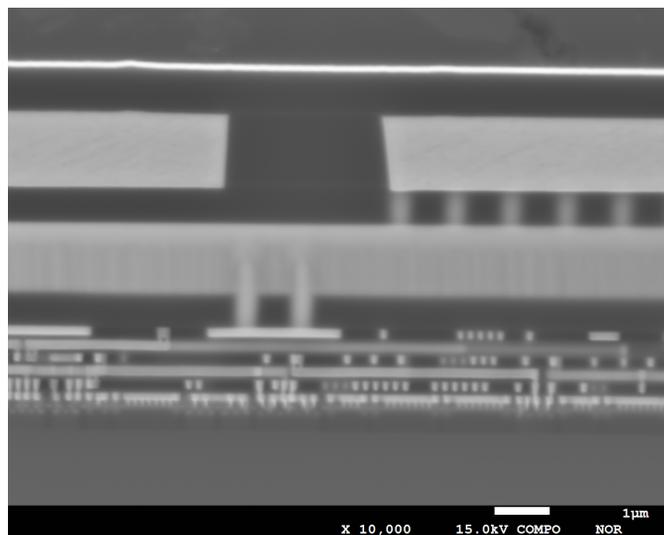
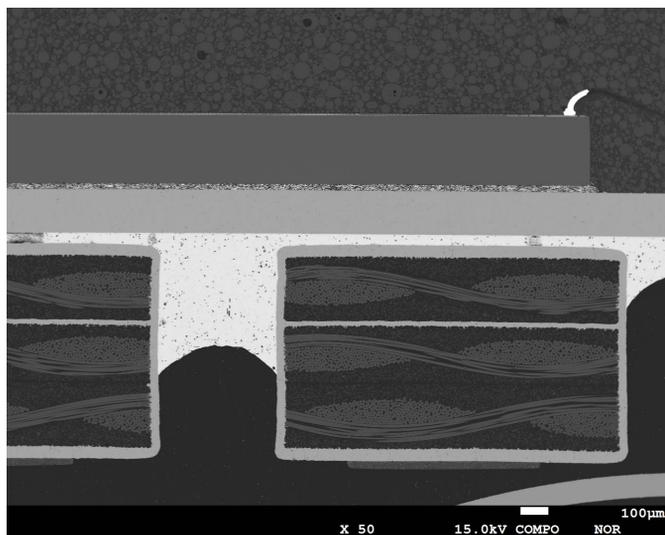


試料調製

- ① 切断
- ② 冷間樹脂埋め (エポフィックス)
- ③ 鏡面研磨 (耐水研磨紙、アルミナ砥粒、コロイダルシリカ)
- ④ カーボン蒸着

SEM観察

<観察条件> 加速電圧：15 kV, 照射電流：30 nA



全元素定性分析 (低倍)

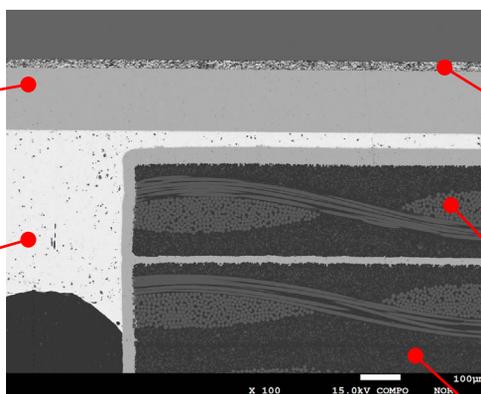
<分析条件> 加速電圧：15 kV, 照射電流：30 nA, ビーム径：10 µm

ZAF Metal			
Element	Mass (%)	Atom (%)	K (%)
C	10.457	19.8640	0.877
Si	98.667	80.1360	97.488

Total	109.124	100.0000	98.365

ZAF Metal			
Element	Mass (%)	Atom (%)	K (%)
C	1.589	11.8948	1.520
O	1.117	6.3571	0.193
Ag	2.799	2.3620	2.893
Sn	103.505	79.3861	101.773

Total	108.990	100.0000	106.378



ZAF Metal			
Element	Mass (%)	Atom (%)	K (%)
C	12.338	46.7335	8.046
O	2.795	7.9475	0.702
Si	0.357	0.5779	0.278
Ni	0.714	0.5531	0.734
Cu	23.718	16.9782	23.448
Ag	64.521	27.2099	59.477

Total	104.443	100.0000	92.686

ZAF Metal			
Element	Mass (%)	Atom (%)	K (%)
C	4.120	18.8004	1.468
Si	1.392	2.7155	0.894
Cu	91.015	78.4842	89.487

Total	96.527	100.0000	91.850

ZAF Metal			
Element	Mass (%)	Atom (%)	K (%)
C	56.082	57.7696	22.000
O	39.966	30.9020	10.055
Al	3.949	1.8106	3.017
Si	19.609	5.9938	11.283
P	0.357	0.1424	0.278
Ca	10.955	3.3816	10.028

Total	124.918	100.0000	56.662

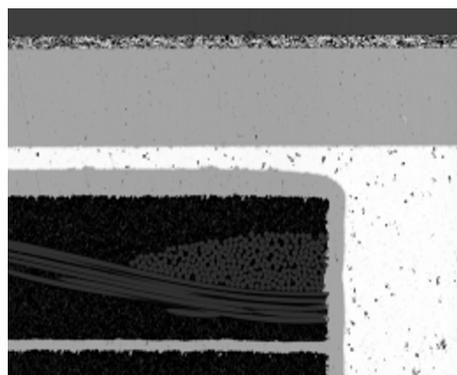
マッピング

<分析条件> 加速電圧：15 kV, 照射電流：30 nA, ビーム径：3 μm , 測定時間：40 ms

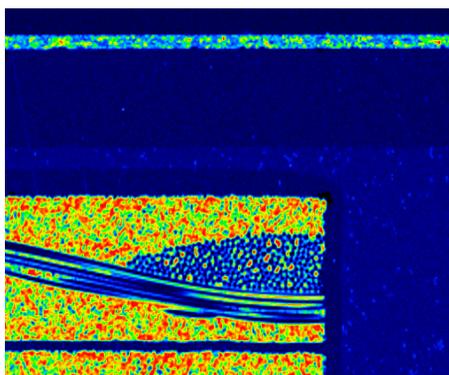
<分光器条件>

Sn : PETH(1ch) $L\alpha 1$
Ag : PETH(1ch) $L\alpha 1$
Al : TAP(2ch) $K\alpha 1$
Si : TAP(2ch) $K\alpha 1$

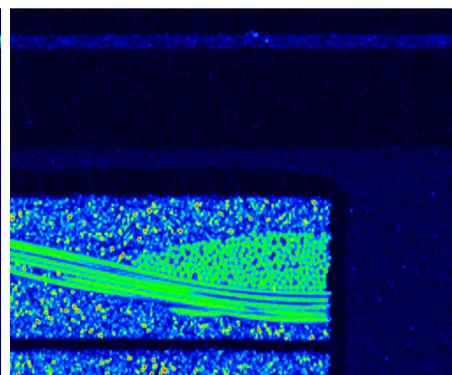
O : LDE1H(3ch) $K\alpha 1$
C : LDE2H(3ch) $K\alpha 1$
Cu : LiFH(4ch) $K\alpha 1$
Ca : PETH(4ch) $K\alpha 1$



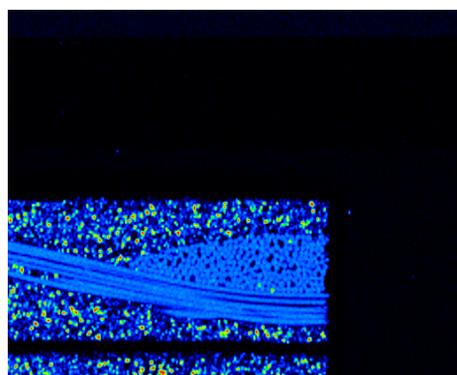
COMPO — 100 um



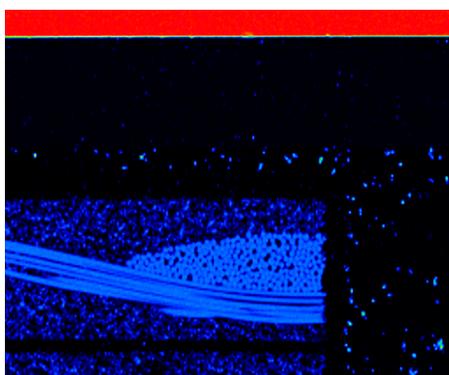
C — 100 um



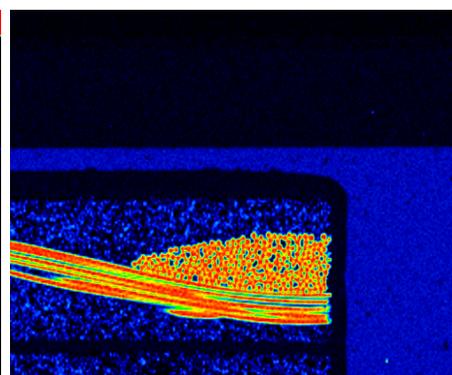
O — 100 um



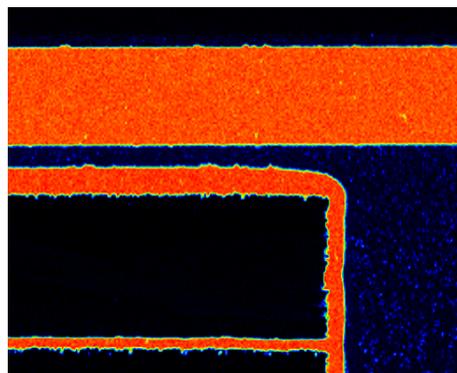
Al — 100 um



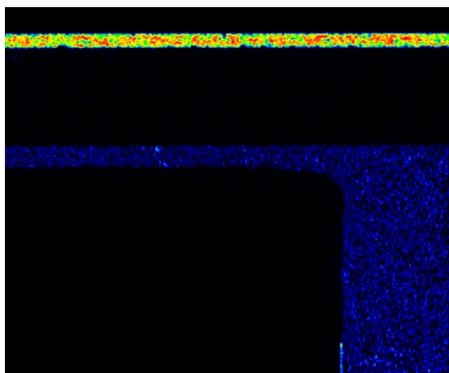
Si — 100 um



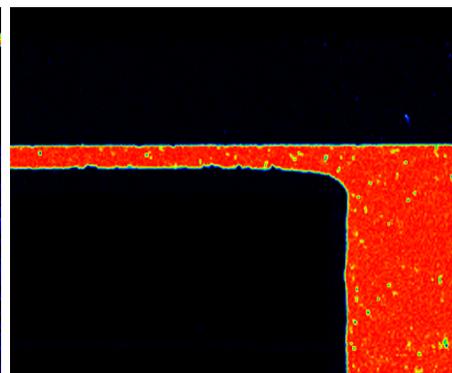
Ca — 100 um



Cu — 100 um



Ag — 100 um



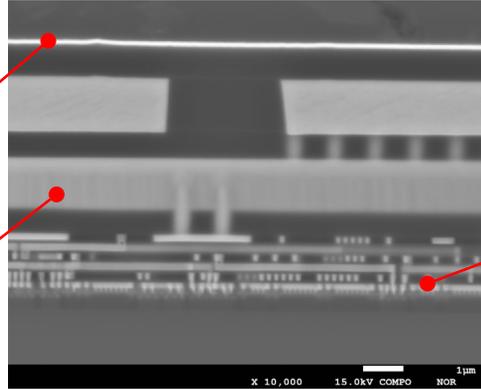
Sn — 100 um

全元素定性分析 (高倍)

<分析条件> 加速電圧：15 kV, 照射電流：30 nA, ビーム径：10 μm

ZAF Metal Element	Mass(%)	Atom(%)	K(%)
C	5.040	10.4784	0.939
N	1.482	2.6406	0.440
O	21.576	33.6712	9.094
Al	25.856	23.9285	22.063
Si	24.490	21.7688	16.338
Cu	5.421	2.1299	5.024
Ta	39.008	5.3827	28.173

Total	122.873	100.0000	82.071



ZAF Metal Element	Mass(%)	Atom(%)	K(%)
C	11.002	29.8125	1.715
O	16.036	32.6191	6.088
Si	29.012	33.6138	24.501
Cu	7.722	3.9548	6.370

Total	63.772	100.0000	38.674

ZAF Metal Element	Mass(%)	Atom(%)	K(%)
C	3.871	17.0905	1.056
O	6.189	20.5107	3.125
Si	11.237	21.2114	7.604
Cu	45.571	38.0237	43.668
Ta	10.796	3.1637	8.162

Total	77.664	100.0000	83.615

マッピング

<分析条件> 加速電圧：15 kV, 照射電流：30 nA, 測定時間：1 ms, 積算回数：20

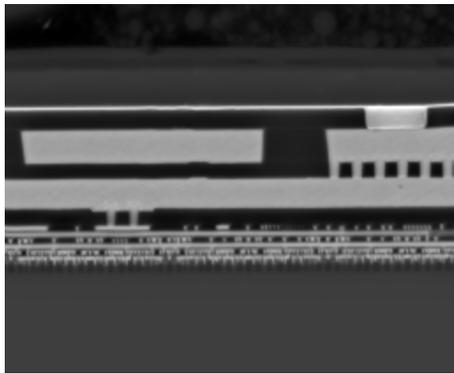
<分光器条件>

Ta : LiFH(1ch) L α 1

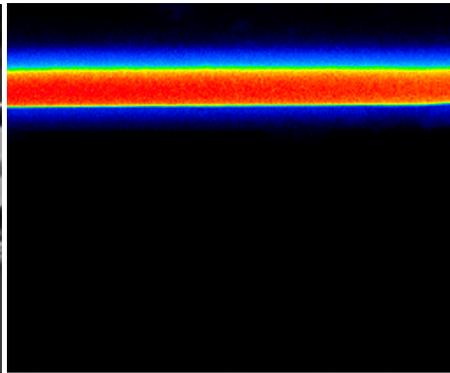
Si : TAP(2ch) K α 1

Al : TAP(2ch) K α 1

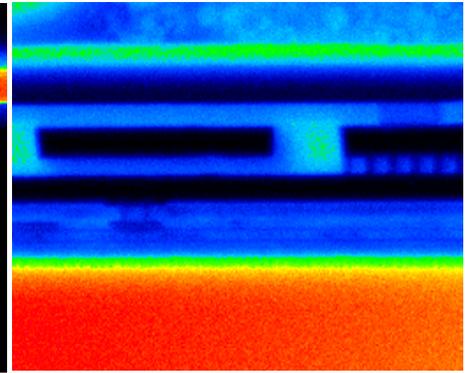
Cu : LiFH(4ch) K α 1



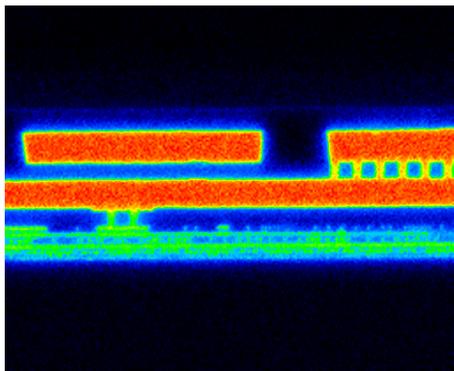
COMPO — 2 μm



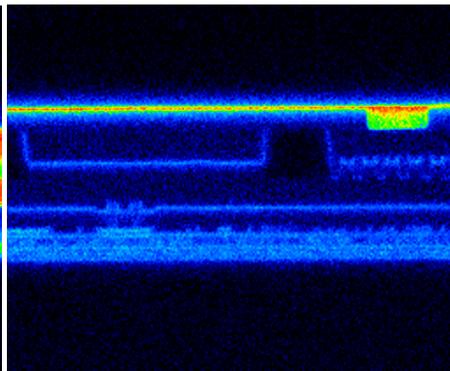
Al — 2 μm



Si — 2 μm



Cu — 2 μm



Ta — 2 μm